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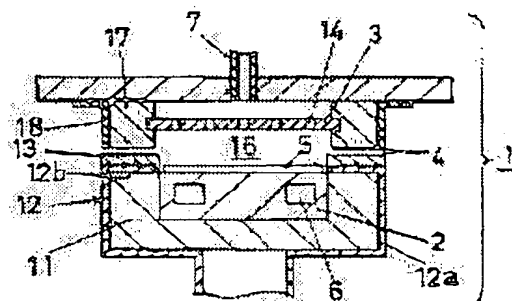
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(54) PLASMA TREATMENT DEVICE

(57)Abstract:

PURPOSE: To provide a plasma treatment device in which the distance between two narrow gaps, formed along the circumference of the counter electrodes, can be widened for the purpose of confining plasma in the counter space of the electrodes.

CONSTITUTION: In a treatment device where the surface of a wafer 5, supported by either of electrodes 2 and 3, is treated by applying high frequency power on one of the two electrodes 2 and 3 provided in parallel with each other in a vacuum treatment chamber 1, a narrow gap part 4, which is narrower than the counter space 16 in the center part, is formed along the circumference of the two electrodes 2 and 3. At the same time, an earth shield 12, covering the outside surface of the electrode 2, is provided through the intermediary of an insulator 11, and an annular extension 12b, protruding into the narrow gap part 4, is provided on the inside of the edge of the earth shield 12.



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